

Amendments to the Abstract

Please replace the Abstract on page 10 of the application with the following paragraph.

A method of fabricating a photomask having a pellicle on a photomask substrate ~~that is disclosed. The method~~ facilitates accurate measurement of ~~the photomask~~ a critical dimension on the photomask, without requiring ~~the~~ removal of the pellicle from the photomask substrate. A first pattern is transferred ~~on~~ onto the photomask ~~[[a]]~~ substrate in a first area, and at least one test pattern is transferred ~~on~~ onto the photomask substrate outside of the first area. ~~The~~ [[A]] pellicle is attached to the photomask substrate, wherein ~~and~~ the pellicle covers the first area, but does not cover the at least one test pattern.